

08/03/01

08-06-01

A

PATENT APPLICATION TRANSMITTAL LETTER
(Large Entity)

Docket No.
F0949

TO THE ASSISTANT COMMISSIONER FOR PATENTS

Transmitted herewith for filing under 35 U.S.C. 111 and 37 C.F.R. 1.53 is the patent application of:

Kai Yang, John Jianshi Wang, and Unsoon Kim

For: **"SELF-ALIGNED GATE FORMATION USING POLYSILICON POLISH WITH PERIPHERAL PROTECTIVE LAYER"**

Enclosed are:

- ☒ Certificate of Mailing with Express Mail Mailing Label No. **EL184649909US**
- ☒ Eight (8) sheets of drawings.
- ☐ A certified copy of a application.
- ☒ Declaration ☒ Signed. ☐ Unsigned.
- ☒ Power of Attorney
- ☐ Information Disclosure Statement
- ☐ Preliminary Amendment
- ☒ Other: **Recordation cover sheet and Assignment: Request and Certification under 35 USC 122(b)(2)(B)(i)**

11036 U.S. PTO
09/922536
08/03/01

CLAIMS AS FILED

For	#Filed	#Allowed	#Extra	Rate	Fee
Total Claims	21	- 20 =	1	x \$18.00	\$18.00
Indep. Claims	2	- 3 =	0	x \$80.00	\$0.00
Multiple Dependent Claims (check if applicable) <input type="checkbox"/>					\$0.00
BASIC FEE					\$710.00
TOTAL FILING FEE					\$728.00

- ☐ A check in the amount of to cover the filing fee is enclosed.
- ☒ The Commissioner is hereby authorized to charge and credit Deposit Account No. **01-0365** as described below. A duplicate copy of this sheet is enclosed.
 - ☒ Charge the amount of **\$728.00** as filing fee.
 - ☒ Credit any overpayment.
 - ☒ Charge any additional filing fees required under 37 C.F.R. 1.16 and 1.17.
 - ☐ Charge the issue fee set in 37 C.F.R. 1.18 at the mailing of the Notice of Allowance, pursuant to 37 C.F.R. 1.311(b).

Dated: **July 31, 2001**

Deborah W. Wenocur
Signature

Deborah W. Wenocur, Reg. No. 40,221
Agent for Applicant
Advanced Micro Devices, Inc., Technology Law Dept.
One AMD Place, M/S 68
P.O. Box 3453
Sunnyvale, CA 94088-3453

cc:

CERTIFICATE OF MAILING BY "EXPRESS MAIL" (37 CFR 1.10)

Applicant(s): Kai Yang, John Jianshi Wang, and Unsoon Kim

Docket No.

F0949

Serial No.

Filing Date

Examiner

Group Art Unit

Invention: **SELF-ALIGNED GATE FORMATION USING POLYSILICON POLISH WITH PERIPHERAL PROTECTIVE LAYER**

I hereby certify that the following correspondence:

paper and fee

(Identify type of correspondence)

is being deposited with the United States Postal Service "Express Mail Post Office to Addressee" service under 37 CFR 1.10 in an envelope addressed to: The Assistant Commissioner for Patents, Washington, D.C. 20231 on

August 3, 2001
(Date)

Deborah W. Wenocur*(Typed or Printed Name of Person Mailing Correspondence)*

Deborah W. Wenocur
(Signature of Person Mailing Correspondence)

EL184649909US*("Express Mail" Mailing Label Number)***Note: Each paper must have its own certificate of mailing.**

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**REQUEST AND CERTIFICATION
UNDER
35 U.S.C. 122(b)(2)(B)(i)**

First Named Inventor

Kai Yang

Title

Self-Aligned Gate Formation Using Polysilicon Polish
With Peripheral Protective Layer

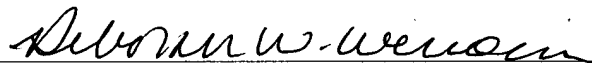
Atty Docket Number

F0949

I hereby certify that the invention disclosed in the attached application **has not and will not be** the subject of an application filed in another country, or under a multilateral agreement, that requires publication at eighteen months after filing. I hereby request that the attached application not be published under 35 U.S.C. 122(b).

July 31, 2001

Date



Signature

Deborah W. Wenocur

Typed or printed name

This request must be signed in compliance with 37 CFR 1.33(b) and submitted with the application **upon filing**.

Applicant may rescind this nonpublication request at any time. If applicant rescinds a request that an application not be published under 35 U.S.C. 122(b), the application will be scheduled for publication at eighteen months from the earliest claimed filing date for which a benefit is claimed.

If applicant subsequently files an application directed to the invention disclosed in the attached application in another country, or under a multilateral international agreement, that requires publication of applications eighteen months after filing, the applicant **must** notify the United States Patent and Trademark Office of such filing within forty-five (45) days after the date of the filing of such foreign or international application. **Failure to do so will result in abandonment of this application (35 U.S.C. 122(b)(2)(B)(iii)).**

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